

Title (en)  
SYSTEM ARCHITECTURE FOR VACUUM PROCESSING

Title (de)  
SYSTEMARCHITEKTUR FÜR EINE VAKUUMBEHANDLUNG

Title (fr)  
ARCHITECTURE DE SYSTÈME DE TRAITEMENT SOUS VIDE

Publication  
**EP 2852469 B1 20190424 (EN)**

Application  
**EP 13780965 A 20130426**

Priority  
• US 201261639052 P 20120426  
• US 2013038530 W 20130426

Abstract (en)  
[origin: US2013287526A1] A system for processing substrates in plasma chambers, such that all substrates transport and loading/unloading operations are performed in atmospheric environment, but processing is performed in vacuum environment. The substrates are transported throughout the system on carriers. The system's chambers are arranged linearly, such that carriers move from one chamber directly to the next. A conveyor, placed above or below the system's chambers, returns the carriers to the system's entry area after processing is completed. Loading and unloading of substrates may be performed at one side of the system, or loading can be done at the entry side and unloading at the exit side.

IPC 8 full level  
**H01L 21/67** (2006.01); **H01L 21/677** (2006.01); **H01L 21/687** (2006.01)

CPC (source: EP US)  
**H01L 21/67173** (2013.01 - EP US); **H01L 21/67709** (2013.01 - US); **H01L 21/67736** (2013.01 - EP US); **H01L 21/67739** (2013.01 - US); **H01L 21/67754** (2013.01 - EP US); **H01L 21/67769** (2013.01 - EP US); **H01L 21/67775** (2013.01 - EP US); **H01L 21/67778** (2013.01 - EP US); **H01L 21/67781** (2013.01 - US); **H01L 21/68742** (2013.01 - US); **H01L 21/68785** (2013.01 - EP US)

Citation (examination)  
• US 2010087028 A1 20100408 - PORTHOUSE KEITH BRIAN [US], et al  
• US 2005232734 A1 20051020 - ELLIOTT MARTIN R [US], et al

Cited by  
EP3528965A4; US11196360B2; US11756816B2; US9543114B2; US10916464B1; US11183411B2; US9525099B2; US9502276B2; US10062600B2; WO2023041263A1

Designated contracting state (EPC)  
AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

DOCDB simple family (publication)  
**US 2013287526 A1 20131031; US 9502276 B2 20161122**; CN 104582863 A 20150429; CN 104582863 B 20160921; EP 2852469 A1 20150401; EP 2852469 A4 20150902; EP 2852469 B1 20190424; JP 2015521373 A 20150727; JP 6231078 B2 20171115; KR 102072872 B1 20200203; KR 20150051935 A 20150513; MY 170824 A 20190904; PT 2852469 T 20190731; SG 11201406893X A 20141127; TW 201401412 A 20140101; TW I518832 B 20160121; US 10115617 B2 20181030; US 2017025300 A1 20170126; WO 2013163622 A1 20131031

DOCDB simple family (application)  
**US 201313871871 A 20130426**; CN 201380033430 A 20130426; EP 13780965 A 20130426; JP 2015509204 A 20130426; KR 20147032318 A 20130426; MY PI2014703146 A 20130426; PT 13780965 T 20130426; SG 11201406893X A 20130426; TW 102114999 A 20130426; US 2013038530 W 20130426; US 201615284450 A 20161003